

Supporting information

to the paper

Preparation and structure of Fe-containing aluminosilicate thin films

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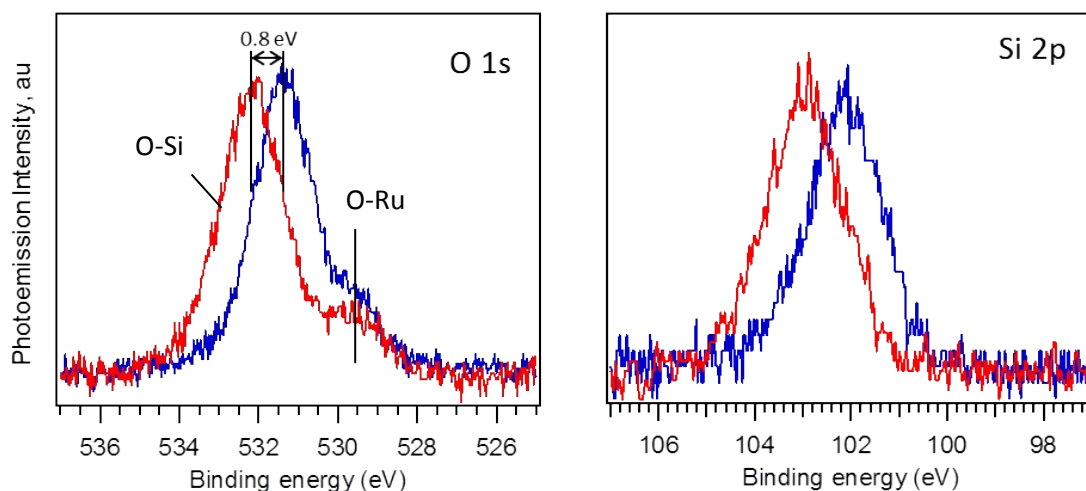


Figure S1. O 1s and Si 2p regions in XP spectra of the silicate bilayer film before (blue) and after (red) 1 ML Fe deposition at 100 K. Note that the signal related to O atoms adsorbed on the Ru surface does not shift.

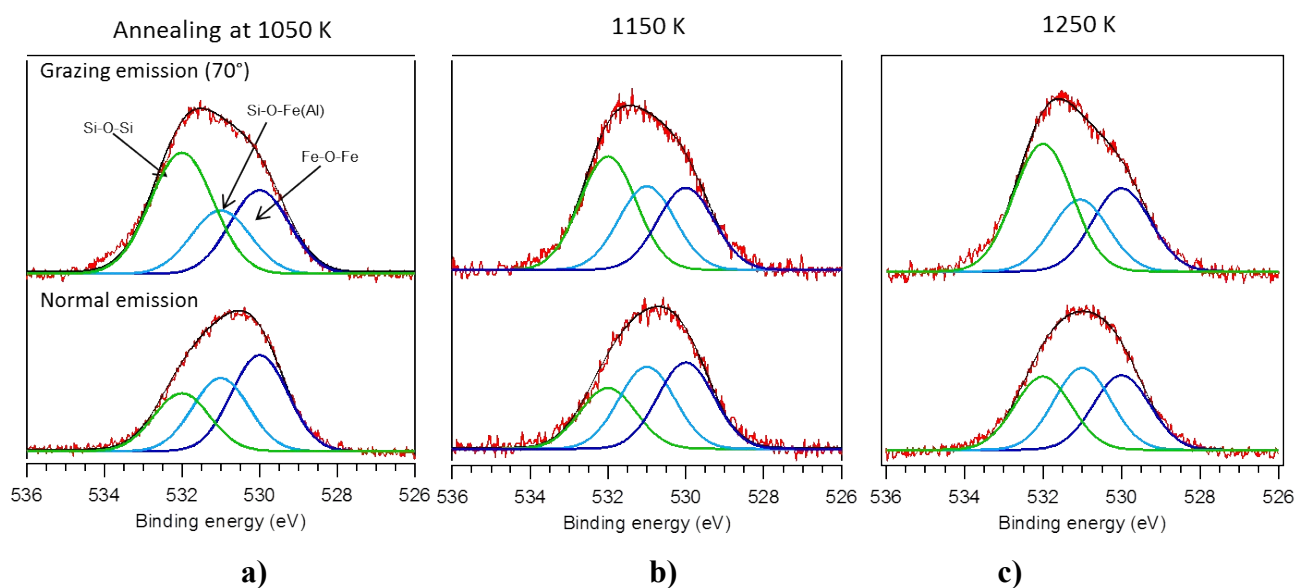


Figure S2. The deconvoluted O 1s spectra at normal and grazing (70°) electron emissions obtained on the $\text{Fe}_{0.5}\text{Al}_{0.13}\text{Si}_{0.37}\text{O}_2$ films prepared at 1050 (a), 1150 (b), and 1250 K (c).

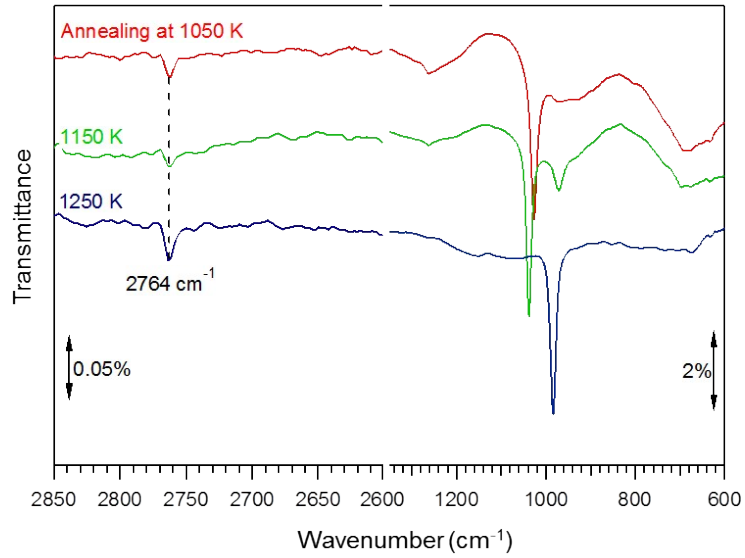


Figure S3. $\nu(\text{OD})$ region and phonon region of IRA spectra measured on $\text{Fe}_{0.5}\text{Al}_{0.13}\text{Si}_{0.37}\text{O}_2$ films (prepared at temperatures as indicated) after hydroxylation with D_2O . The spectra only revealed a band at 2764 cm^{-1} characteristic for terminal silanols.